

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	709	electrode and sacrificial and membrane and (etch\$3 or pattern\$3) and pad	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 08:49
L3	1	"5873154".PN.	USPAT; USOCR	OR	OFF	2005/09/08 09:03
L6	715	electrode same (sacrificial or remov\$3 or polyimide) same (membrane or SiN or "silicon nitride") same (etch\$3 or pattern\$3) same pad	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 08:23
L7	440886	"micro-electromechanical system" or MEMS	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 08:24
L8	54	6 and 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 08:24
L10	752	substrate same (polyimide or polymer) same PECvd	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 08:34
L12	21487	"flexible substrate"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 08:49
L16	268	electrode and sacrificial and membrane and (etch\$3 or pattern\$3) and (pad or contact) and PECvd	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 09:06
L17	128	electrode and (sacrificial or removable) and membrane and (etch\$3 or pattern\$3) and (pad or contact) and PECvd and (SiN or passivation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 09:07

L18	15	nam-yun-woo.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 09:07
L19	44	lee-suk-han.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 09:18
L20	2	"6677709".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/08 09:18